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Patent  
Attorney's Docket No. 015290-517

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Patent Application of	)	
	)	
Tuqiang NI et al.	)	Group Art Unit: Not Yet Assigned
	)	
Application No.: Not Yet Assigned	)	Examiner: Not Yet Assigned
	)	
Filed: February 21, 2001	)	
	)	
For: GAS INJECTION SYSTEM FOR	)	
PLASMA PROCESSING	)	
	)	
	)	

**PRELIMINARY AMENDMENT**

Assistant Commissioner for Patents  
Washington, D.C. 20231

Sir:

Prior to examination, please amend the above-identified application as follows:

**IN THE CLAIMS:**

Please cancel Claim 1 and add new Claims 25-36 as follows:

~~25.~~ A gas injector for supplying process gas to a plasma processing chamber wherein a semiconductor substrate is subjected to plasma processing, the gas injector comprising:  
gas injector body sized to extend through a chamber wall of the processing chamber such that a distal end of the gas injector body is exposed within the processing chamber, the gas injector body including a plurality of gas outlets adapted to supply process gas into the processing chamber.

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